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This disadvantage is not encountered when the polymeric form, Nafion-TMS is used, which resists hydrolytic cleavage^{2,4,5,6} considerably. However, monomeric trimethylsilyl triflate is advantageous over the polymer²; for example, because of its higher electrophilicity it may be used to cleave cyclopropanes at ambient temperature⁴. A cheap *in situ* preparation giving only inert by-products therefore appeared desirable.

Trimethylsilyl triflate (2) has so far been accessible by the following procedures none of which meets with all of the above requirements: Treatment of chlorotrimethylsilane with (expensive) silver trifluoromethanesulfonate in boiling benzene⁷ or with neat trifluoromethanesulfonic acid (1) at 120 °C for several hours and driving off the hydrochloric acid formed⁸. Further, compound 2 has been prepared *in situ* by reaction of 1 with phenyltrimethylsilane⁹ or allyltrimethylsilane¹⁰, both of which are expensive reagents.

The reaction of trifluoromethanesulfonic acid (1) with tetramethylsilane should combine all of the desired advantages but this reaction has been reported⁷ not to proceed even at reflux temperature with a reaction time of 48 h. This negative result is surprising since sulfuric acid reacts with tetramethylsilane at room temperature (1.5 h) to afford trimethylsilyl sulfate¹¹. The even stronger trifluoromethanesulfonic acid (1) should therefore also be expected to react with tetramethylsilane. We have now indeed found that mixing of trifluoromethanesulfonic acid (1) with (commercial or redistilled) tetramethylsilane under argon at room temperature causes evolution of methane (analyzed by G.L.C. using a 48 m glass capillary column OV1 at 0 °C and by mass spectrometry); after 1 h, formation of trimethylsilyl triflate (2) is complete as evidenced by ¹H-N.M.R. monitoring.

$$F_{3}C - \stackrel{\circ}{\underset{\parallel}{\text{S}}} - OH + Si(CH_{3})_{4} \longrightarrow F_{3}C - \stackrel{\circ}{\underset{\parallel}{\text{S}}} - O - Si(CH_{3})_{3} + CH_{4}$$

Neither trifluoroacetic acid, which is similar in acidity to sulfuric acid, nor the less acidic methanesulfonic acid react with tetramethylsilane, not even at elevated temperatures.

Trimethylsilyl Trifluoromethanesulfonate (2, Trimethylsilyl Triflate): Trifluoromethanesulfonic acid (1; 1.5 g, 10 mmol) and tetramethylsilane (1.1 g, 12.5 mmol) are mixed under an argon atmosphere at room temperature. After 1 h, evolution of methane ceases and formation of 2 is complete. Distillation of the mixture affords product 2 as a colorless liquid; yield: 2.2 g (99%); b.p. 40 °C/11 torr (Ref. 7, b.p. 36.5 °C/10 torr); purity: 96% (G.L.C. 50 m glass capillary column, OV 1). $C_4H_9F_3O_3SSi$ (222.2).

M.S. (70 eV): $m/e = 222 \text{ (M}^+)$, 207, 147, 77, 73, 69. ¹H-N.M.R. (CDCl₃/TMS_{int}): $\delta = 0.50 \text{ ppm (cf. Ref.}^{10}$).

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Trimethylsilyl trifluoromethanesulfonate (2, TMS triflate) is commercially available and widely used in various synthetic applications²⁻⁶. The reagent is rapidly hydrolyzed in the air.

A Convenient in situ Preparation of Trimethylsilyl Trifluoromethanesulfonate 1

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